

# Non Destructive Testing: Characterization of a crack with the measurement of an electric resistance

## 2D Textbook Case Summary

Program	Dimension	Physics	Application	Work area
Flux	2D	Electric	Kinetic	NDT

Characterization of the geometry of a crack with the measurement of an electric resistance. This example shows how to use one of the existing Non Destructive Testing methods (NDT by conduction or by current injection).

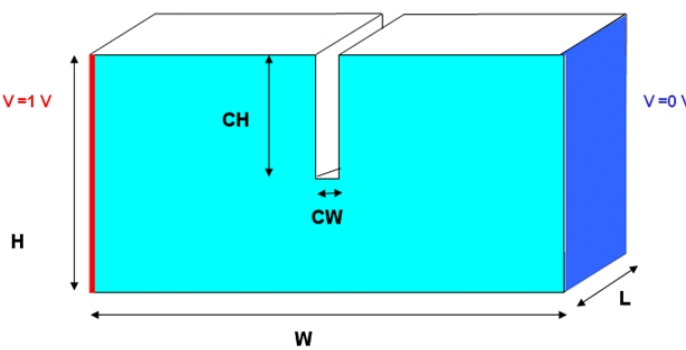
**Objective:** Computation of the electric resistance of a cracked component. The parameters the user can change are:

- crack’s width (CW)
- crack’s height (CH)
- resistivity of the component’s material (RHO)

### Theoretical reminders

Analytical computation of elementary electric resistances of components shaped as parallelepipeds or prisms.

$$dR = \frac{\rho \times dl}{S(h)}$$

Illustration	Main characteristics
	<ul style="list-style-type: none"> <li>• Rated potential difference <math>V = 1 \text{ V}</math></li> <li>• Rated component dimensions: <math>W \times H \times L = 100 \text{ mm} \times 50 \text{ mm} \times 40 \text{ mm}</math></li> <li>• Rated material resistivity (copper) <math>RHO = 1.7 \text{ E-}8 \text{ } \Omega \cdot \text{m}</math></li> <li>• Rated crack’s width: <math>CW = 5 \text{ mm}</math></li> <li>• Rated crack’s height: <math>CH = 45 \text{ mm}</math></li> </ul>

# Results

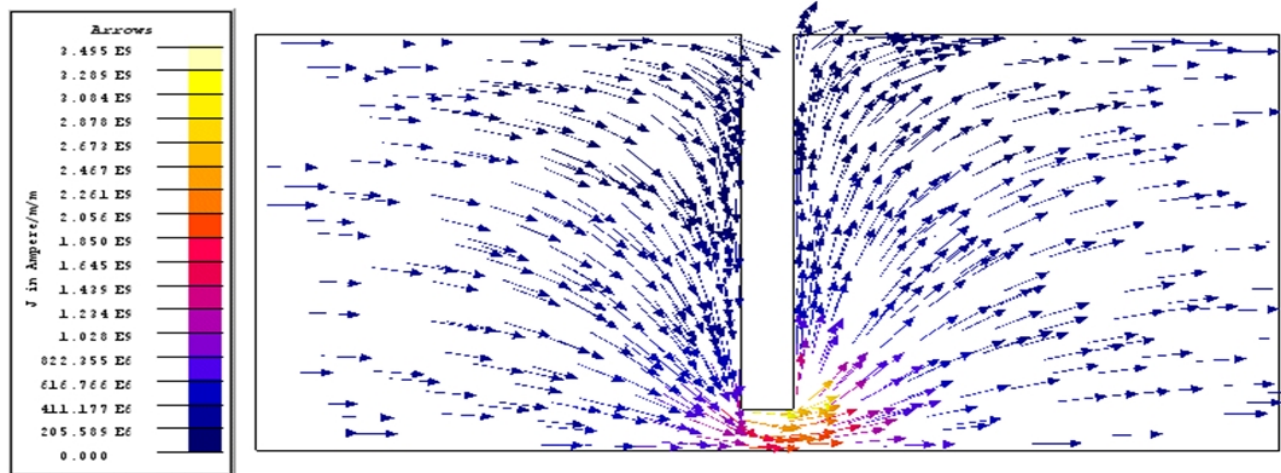


Figure 1: Flow of current at rated working point

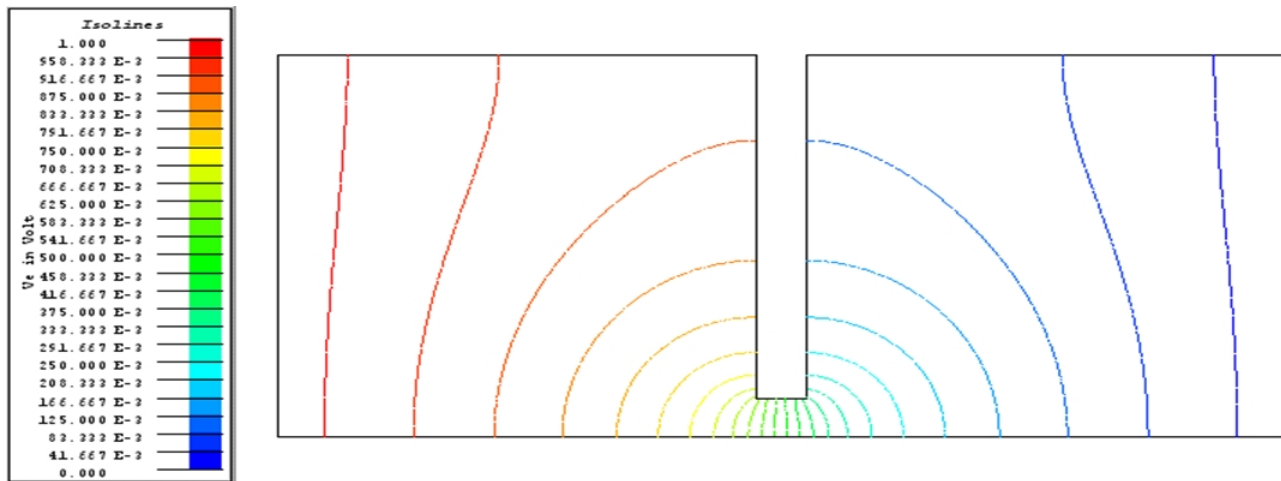


Figure 2: Equipotential lines at rated working point

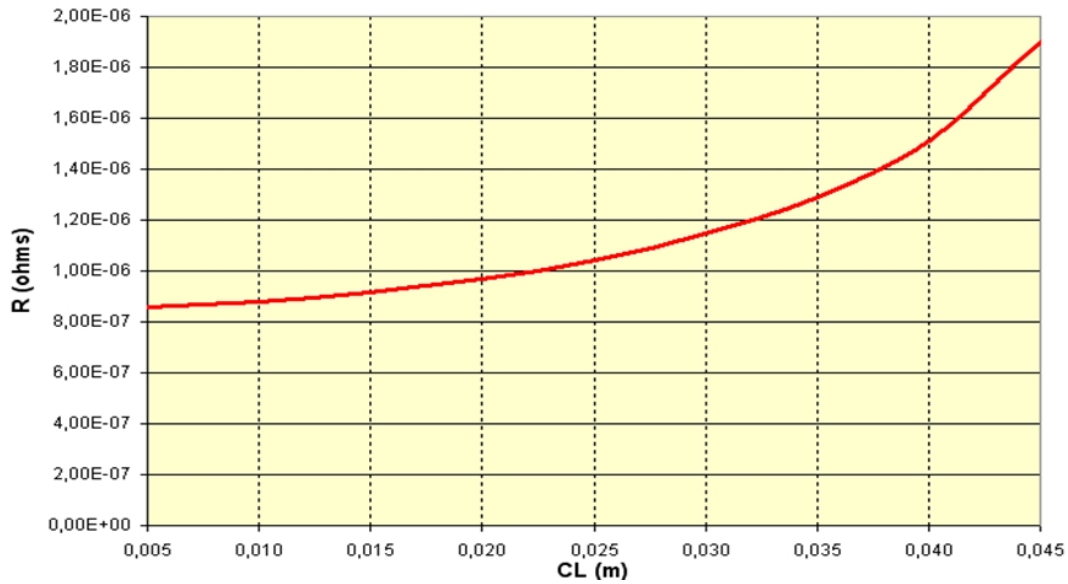


Figure 3: Electric resistance's (R) evolution as a function of the crack's height (CH) (the other parameters are rated)

**To go further:**

- Similar study, but with a stiff current density
- Similar analysis for more complex 3D type devices etc.

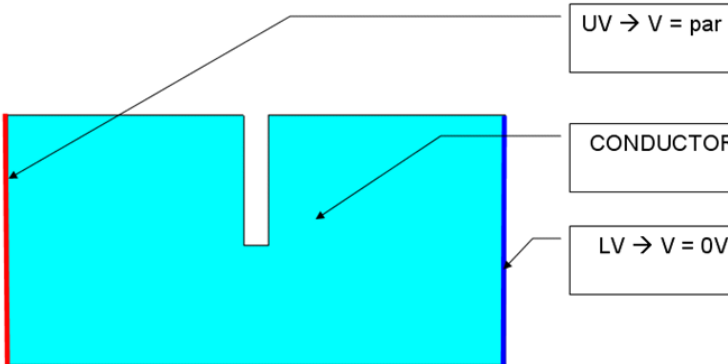
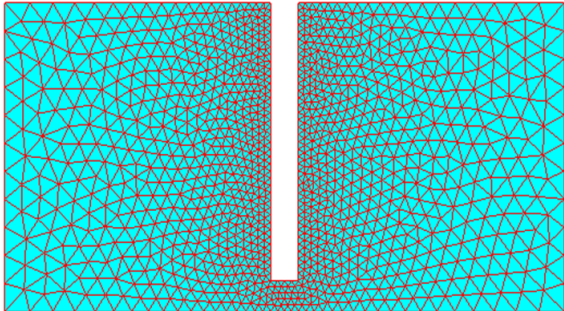
# Model in Flux

## Domain

Dimension	2D	Depth	L
Length unit.	mm	Angle unit.	degrees

Application	Electro kinetic
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## Geometry / Mesh

Full model in the FLUX environment	Mesh
 <p>UV → V = par</p> <p>CONDUCTOR</p> <p>LV → V = 0V</p>	

Mesh	2 <sup>nd</sup> order type	Number of nodes	4633
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## Input Parameters

Name	Type	Description	Rated value
L	Geometrical	Material length	40 mm
W	Geometrical	Material width	100 mm
H	Geometrical	Material height	50 mm
CH	Geometrical	Crack height	45 mm
CW	Geometrical	Crack width	5 mm
RHO	Physical	Material resistivity	$1.7 \text{ E}^{-8} \text{ W.m}$
V	Physical	Potential difference	1 V

## Material Base

NAME	MATERIAL
B(H) model	-
Magnetic property	-
J(H) model	Isotropic resistivity
Electrical property	RHO
D(E) model	-
Dielectric property	-
K(T) model	-
K(T) characteristics	-
RCP(T) model	-
RCP(T) characteristics	-

## Regions

NAME	COMPONENT	UV	LV
Nature	Surface region	Line region	Line region
Type	Conductive region	Stiff electric potential	Stiff electric potential
Material	MATERIAL	-	-
Mechanical Set	-	-	-
Corresponding circuit component	-	-	-
Electrical characteristics	-	V	0
Current source	-	-	-
Thermal characteristics	-	-	-
Possible thermal source	-	-	-

## Solving process options

Type of linear system solver	Automatically chosen	Parameters	Automatically defined
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Type of non-linear system solver	Newton Raphson	Precision	0.0001	Nb iterations	100
		Method for computing the relaxation factor		Automatically chosen	

## Solving

Scenario	Name of parameter	Controllable parameter	Variation method	Interval definition	Step selection
SCENARIO	CH	Geometrical	Step value	5 mm to 45 mm	5 mm

# Annex

## Analytical computation of the resistance

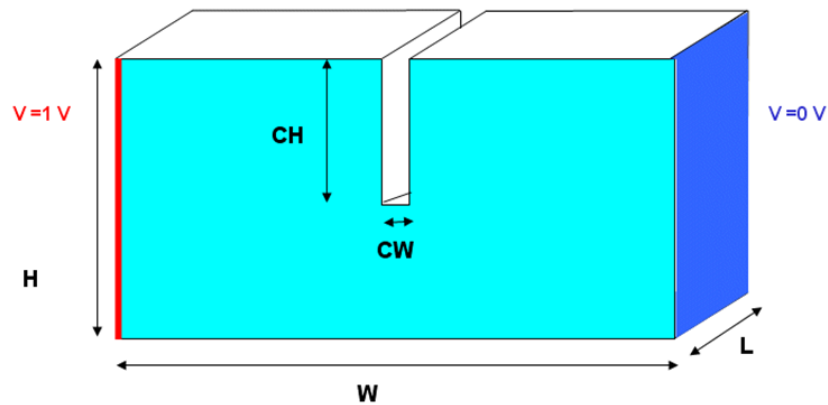
Maxwell equation:  $E = -\text{grad}V$

Ohm's Law:  $J = \sigma E$

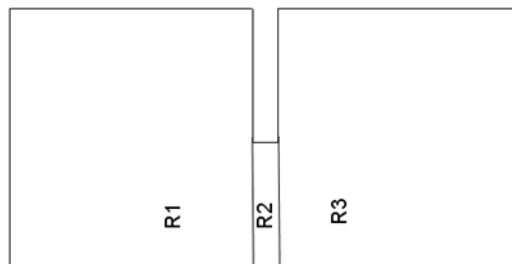
Resistance computation:  $dR = \rho \times \frac{dh}{S(h)}$

## General remarks

The analytical method consists of calculating the values of elementary electric resistances of components described as parallelepipeds (model 1) or parallelepipeds + prisms (model 2). The elementary resistances are then connected in series and a global equivalent resistance can be calculated.



## Model 1 :

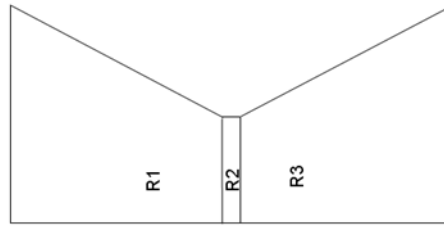


With:  $R = R1 + R2 + R3$

$$R1 = R3 = \rho \times \frac{W - CW}{2 \times H \times L}$$

$$R2 = \rho \times \frac{CW}{(H - CH) \times L}$$

## Model 2



With:  $R=R1+R2+R3$

$$R1 = R3 = \rho \times \frac{CW}{2 \times L \times (H - CH)} \quad R2 = \rho \times \frac{W - CW}{L \times CH} \times \ln\left(\frac{H}{H - CH}\right)$$

## Notations and symbols

Name	Description	Unit
R	Material resistance	$\Omega$
$\rho$	Material resistivity	$\Omega.m$
H	Material height	m
L	Material length	m
W	Material width	m
CH	Crack height	m
CW	Crack width	m

## Numerical applications

### R computation

Let's calculate the value of the electric resistance with different methods when component parameters are the following:

- Potential difference  $V = 1 \text{ V}$
- Component dimensions:  $W \times H \times L = 100 \text{ mm} \times 50 \text{ mm} \times 40 \text{ mm}$
- Material resistivity (copper):  $RHO = 1.7 \text{ E}^{-8} \Omega.m$
- Crack width :  $CW = 5 \text{ mm}$
- Crack height :  $CH = 45 \text{ mm}$

### Computation with method 1

$$R1 = R3 = \rho \times \frac{W - CW}{2 \times H \times L} = 1.7 \times 10^{-8} \times \frac{(100 - 5) \times 10^{-3}}{2 \times 50 \times 40 \times 10^{-6}} = 403 n\Omega$$



$$R2 = \rho \times \frac{CW}{(H-CH) \times L} = 1.7 \times 10^{-8} \times \frac{5 \times 10^{-3}}{(50-45) \times 40 \times 10^{-6}} = 425n\Omega$$

$$R = R1 + R2 + R3 = 1.23\mu\Omega$$

### Computation with method 2

$$R1 = R3 = \rho \times \frac{CW}{2 \times L \times (H-CH)} = 1.7 \times 10^{-8} \times \frac{5 \times 10^{-3}}{2 \times 40 \times (50-45) \times 10^{-6}} = 212n\Omega$$

$$R2 = \rho \times \frac{W-CW}{L \times CH} \times \ln\left(\frac{H}{H-CH}\right) = 1.7 \times 10^{-8} \times \frac{95 \times 10^{-3}}{40 \times 45 \times 10^{-6}} \times \ln\left(\frac{50}{5}\right) = 2.06\mu\Omega$$

$$R = R1 + R2 + R3 = 2.46\mu\Omega$$

### Result obtained with Flux

At this working point, Flux calculates a resistance of  $R = 2.46\mu\Omega$